CONTRIBUTORS VOLUME 22

Numbers in parentheses indicate the pages on which the authors' contributions begin.

BHAVIK R. BAKSHI, *Department of Chemical Engineering, Ohio State University, Columbus, Ohio 43210* (313, 347, 485)

CHONGHUN HAN, *Laboratory for Intelligent Systems in Process Engineering, Department of Chemical Engineering, Massachusetts Institute of Technology, Cambridge, Massachusetts 02139* (313)

ALEXANDROS KOULOURIS, *Laboratory for Intelligent Systems in Process Engineering, Department of Chemical Engineering, Massachusetts Institute of Technology, Cambridge, Massachusetts 02139* (437)

RAMACHANDRAN LAKSHAMANAN, *Department of Chemical Engineering, University of Edinburgh, Edinburgh, Scotland, United Kingdom* (313)

MATTHEW J. REALFF, *School of Chemical Engineering, Georgia Institute of Technology, Atlanta, Georgia 30332* (549)

PEDRO M. SARAIVA, *Department of Chemical Engineering, University of Coimbra, 3000 Coimbra, Portugal* (377)

GEORGE STEPHANOPOULOS, *Laboratory for Intelligent Systems in Process Engineering, Department of Chemical Engineering, Massachusetts Institute of Technology, Cambridge, Massachusetts 02139* (437, 485)